

Tool ID: 319  
Tool Location: 102

Equipment Information Sheet  
**Veeco Savannah ALD**

**Manager:** Jeremy Clark  
**Backup:** Mac McMurdy

607-254-6487  
607-254-4813

Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.

**SAFETY**

- Uses highly toxic & reactive / pyrophoric precurses for film deposition. Materials are monitored by TGMCS.

**USAGE RESTRICTIONS**  
**SCHEDULING/SIGN-UP RESTRICTIONS**  
**MATERIALS COMPATIBILITY CATEGORY**

Minimum Tool Time: 15 minutes

Tool Category 4: Glass and Metal Categories	
Allowed	Not Allowed
Tool category 1/1E, 2, and 3 materials	
Silicon Based Substrates and Films	No CNF Class A metals
III/V compound Semiconductors	<b>No Exposed CNF Group B metals- <i>metals can be buried/covered with staff approval</i></b>
Glass Substrates	Cannot be used as an etch stop
PECVD and ALD Films	
Buried Class B Metals with approval	
Organic/Bio Materials prepped w/o Salt Buffers	
Cured organics and baked Photoresist	No High Vapor pressure materials

**High Vapor Pressure Metals and Compounds**are materials that have a vapor pressure above 1e-6 Torr at 400 C.

**Additional Material Restrictions and Exceptions**

- All sizes from pieces to 200mm wafers allowed

Last Updated: 12/20/2022